

1762

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Katsuhisa YUDA, et al.

Application No.: 09/818,972

Filed: March 27, 2001

For: METHOD OF FORMING SILICON OXIDE
FILM AND FORMING APPARATUS
THEREOF

Art Unit: 1762

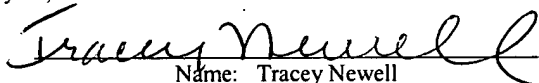
Examiner: Wesley D. Markham

Attorney Docket: GOM-02001

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I hereby certify that the foregoing documents are being deposited with the United States Postal Service as first class mail, in an envelope addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on this date of July 22, 2003.


Name: Tracey Newell

RESPONSE TO RESTRICTION REQUIREMENT

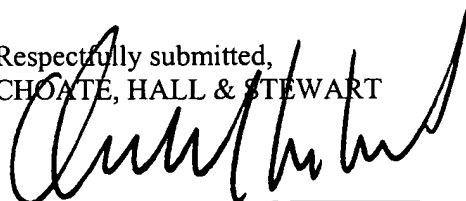
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated June 26, 2003, in which restriction was required, Applicant elects Group II, claims 7-12, drawn to an apparatus for forming a silicon oxide film on a substrate.

Favorable consideration and allowance are earnestly solicited. Should there be any questions after reviewing this paper, the Examiner is invited to contact the undersigned at 617-248-4038.

Respectfully submitted,
CHOATE, HALL & STEWART



July 22, 2003

Date

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